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- (71) Applicant (*for all designated States except US*): **DSM IP ASSETS B.V.** [NL/NL]; Het Overloon 1, NL-6411 Te Heerlen (NL).
- (72) Inventors; and
- (75) Inventors/Applicants (*for US only*): **SHAHAB, Jahromi** [NL/NL]; Foldersdreef 32, NL-6216 TE Maastricht (NL). **DERKS, Franciscus, Johannes, Marie** [NL/NL]; In de Hoven 12, NL-6093 DK Heythuysen (NL). **LYAPUNOV, Andrey, Yaroslavovich** [RU/RU]; Dmitriya Ulyanova street 1/61, Apt., 141, 119333 Moscow (RU).
- (74) Agent: **DORRESTIJN, Antoon**; DSM Intellectual Property, P.O. Box 9, NL-6160 MA Geleen (NL).
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(54) Title: DISSOLUTION INHIBITORS IN PHOTORESIST COMPOSITIONS FOR MICROLITHOGRAPHY

(57) Abstract: The invention relates to photoresist composition suitable for use at 10-165 nm comprising: (a) a polymeric binder (b) a photoactive compound (c) a dissolution inhibitor, the dissolution inhibitor comprising at least (i) two aromatic groups, (ii) fluorine and (iii) a blocked acid group which when unblocked has a pKa < 12. Preferred dissolution inhibitors are optionally blocked bisphenol derivates in which the bridging carbon atom is substituted with a fluorinated aliphatic group.

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